

2011/10/14-15, PF研究会
「磁性薄膜を究める: キャラクタリゼーション
から新奇材料の創製へ」

表面修飾による Fe_3O_4 最表面 ハーフメタル性回復現象

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¹物質・材料研究機構 極限計測ユニット

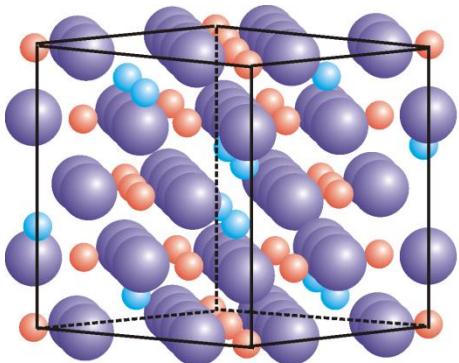
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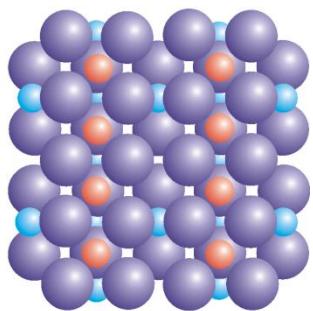
Bulk Fe_3O_4

1. 物性、結晶構造

• $T_c=858 \text{ K}$ 、逆スピネル構造



Bulk



Ideal (100) surface



O

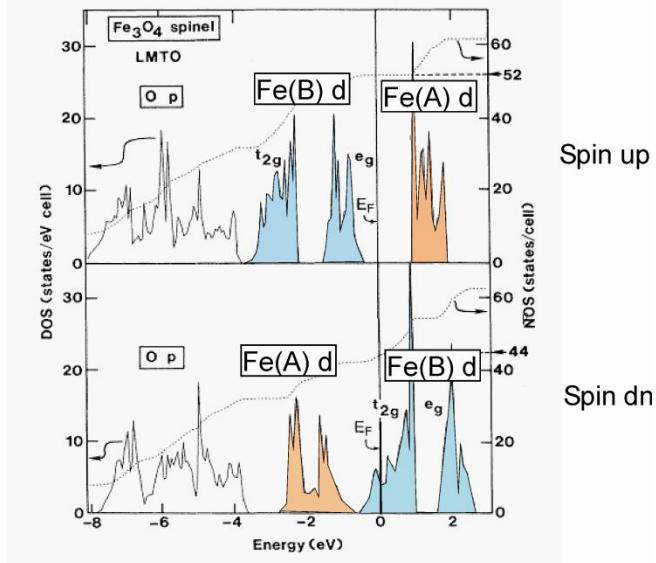


Fe-A site
(Fe^{3+})



Fe-B site
($\text{Fe}^{2+}, \text{Fe}^{3+}$)

2. 電子状態計算



Z. Zhang and S. Satpathy,
PRB 44, 13319 (1991)

Spin up -- band gap

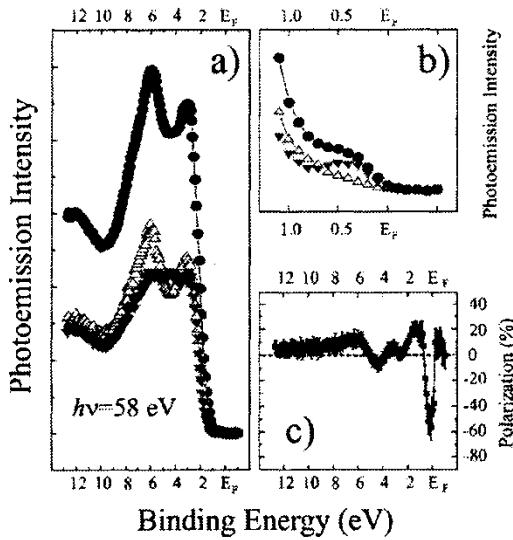
Spin down --- metallic

→ $P(E_F) = -100\%$

Fe_3O_4 表面,界面スピン偏極

1. SPES

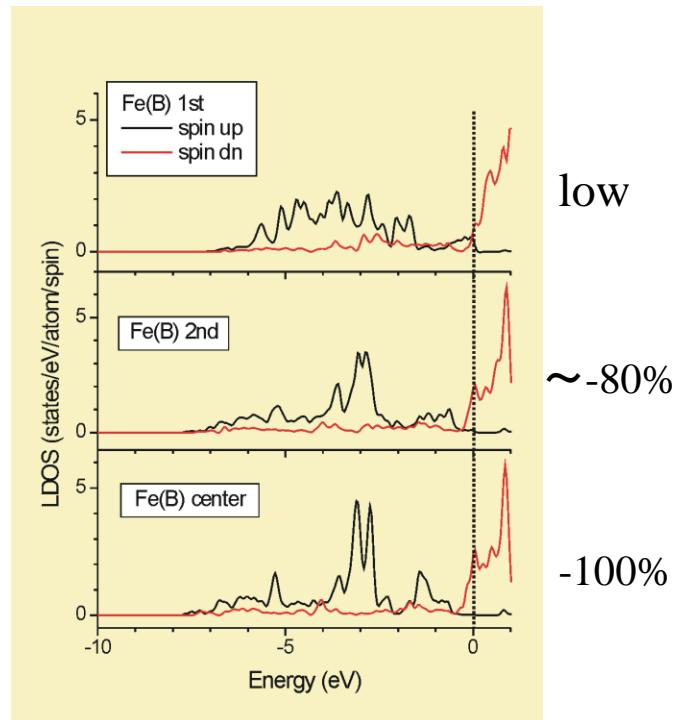
- (100) : $P(E_F) = -40 \sim -60\%$
- (111) : $\sim -80\%$



SPES
--- probing depth
 $\rightarrow P(E_F)$ at topmost surface?

[M. Fonin et al.,
Phys. Rev. B 72, 104436(2005)]

表面電子状態計算
($\text{Fe}_3\text{O}_4(100)$ 理想表面)



2. 伝導測定

- TMR --- -26 % (RT)

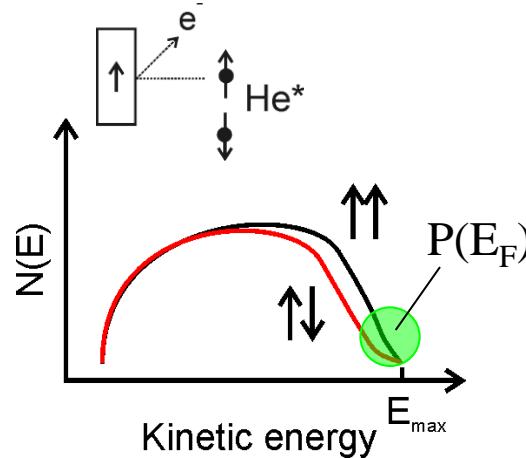
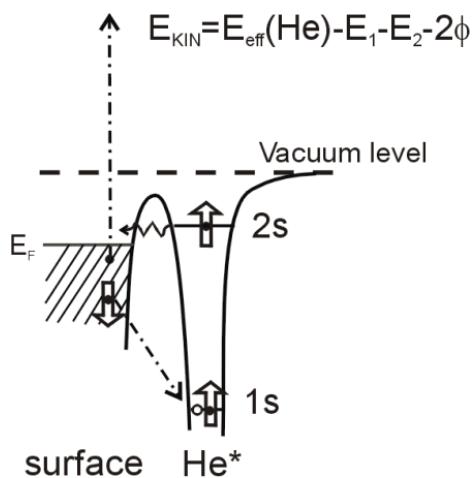
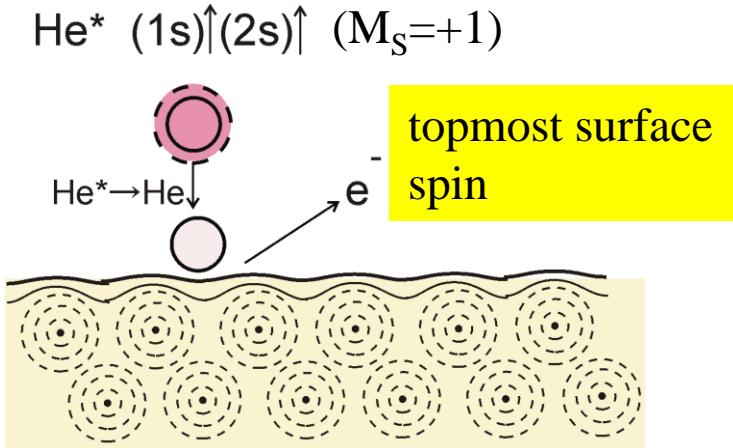
[T. Kado, APL, 92, 092502 (2008)]

本研究の内容

1. スピン偏極Heビーム法
→ $\text{Fe}_3\text{O}_4(100)$ 最表面 E_F スピン偏極
(5%以下)

2. 表面の水素終端
→ $P(E_F)$ が著しく増大 (室温で-50%以上)
ハーフメタル性回復 (計算)

スピン偏極He^{*}ビームによる表面計測



$$N_{\uparrow}(E_{\text{max}} - E) = \int_0^E D_{\downarrow}(E') D_{\text{tot}}(E - E') dE'$$

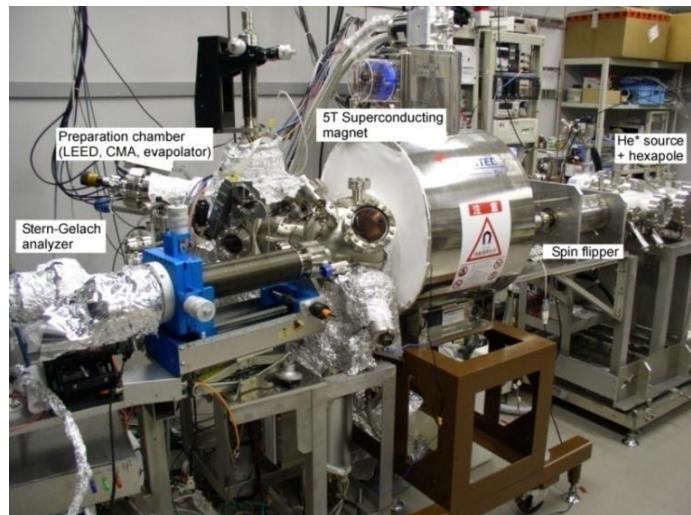
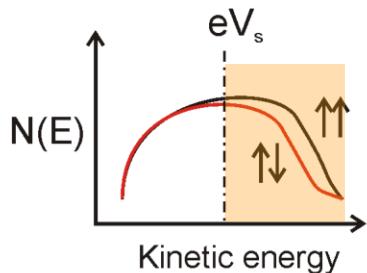
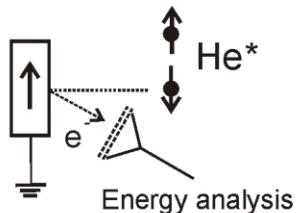
$$N_{\uparrow}(E_{\text{max}}) \propto D_{\downarrow}(E_F)$$

$$A = \frac{N_{\uparrow} - N_{\downarrow}}{N_{\uparrow} + N_{\downarrow}}$$

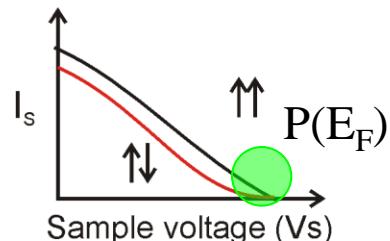
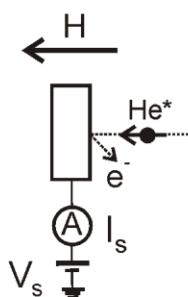
$$\rightarrow A(E_{\text{max}}) \cong -P(E_F)$$

強磁場下表面スピニ偏極計測

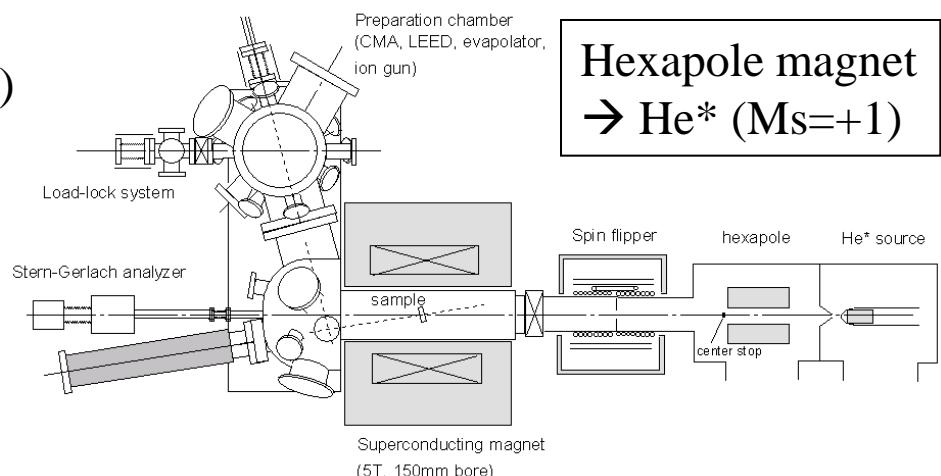
1. SPMDS



2. sample current (H—allowed)



$$I(V_s) = \int_{eV_s}^{\infty} N(E)dE$$



Sample

- Fe₃O₄(100) surface

- 1, epitaxial film (20 nm)

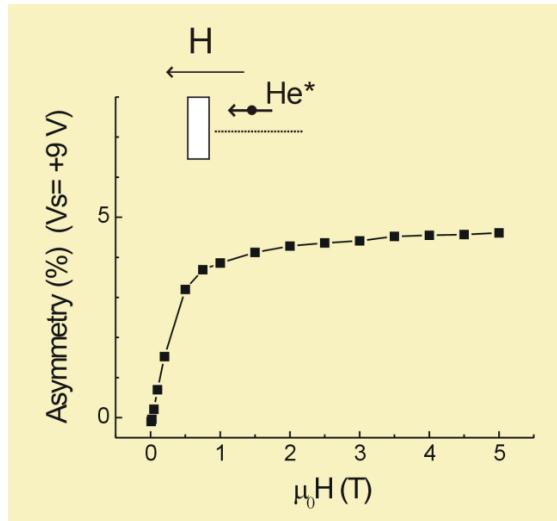
- Fe deposition (0.1nm/min)
at P(O₂)=3x10⁻⁶ Torr
 - Ts=250-300°C

- 2, natural single crystal

- sputter+annealing (500°C)
 - 300°C annealing at P(O₂)~10⁻⁶ Torr

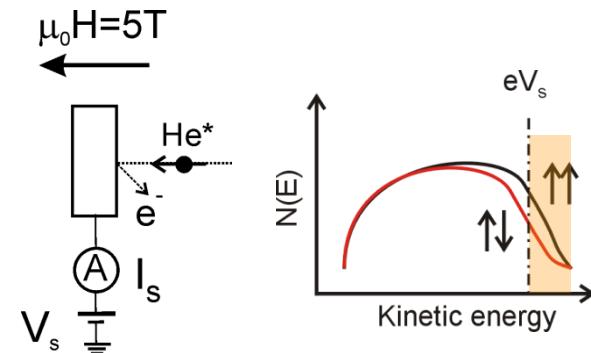
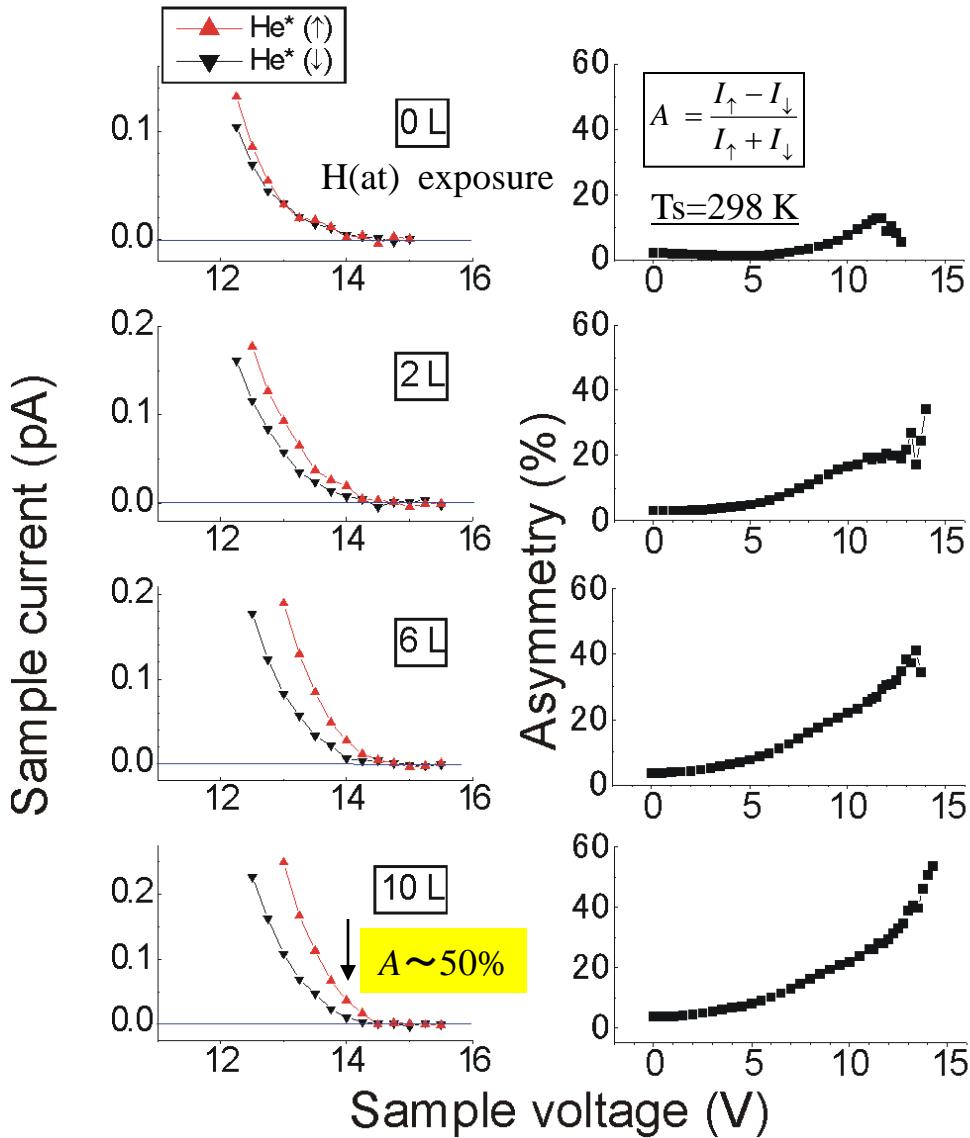
- Atomic H

- thermal dissociation of H₂



Fe₃O₄(100)薄膜の最表面磁化曲線
(磁場は面垂直方向)

$\text{Fe}_3\text{O}_4(100)/\text{MgO}(100)$ +atomic H

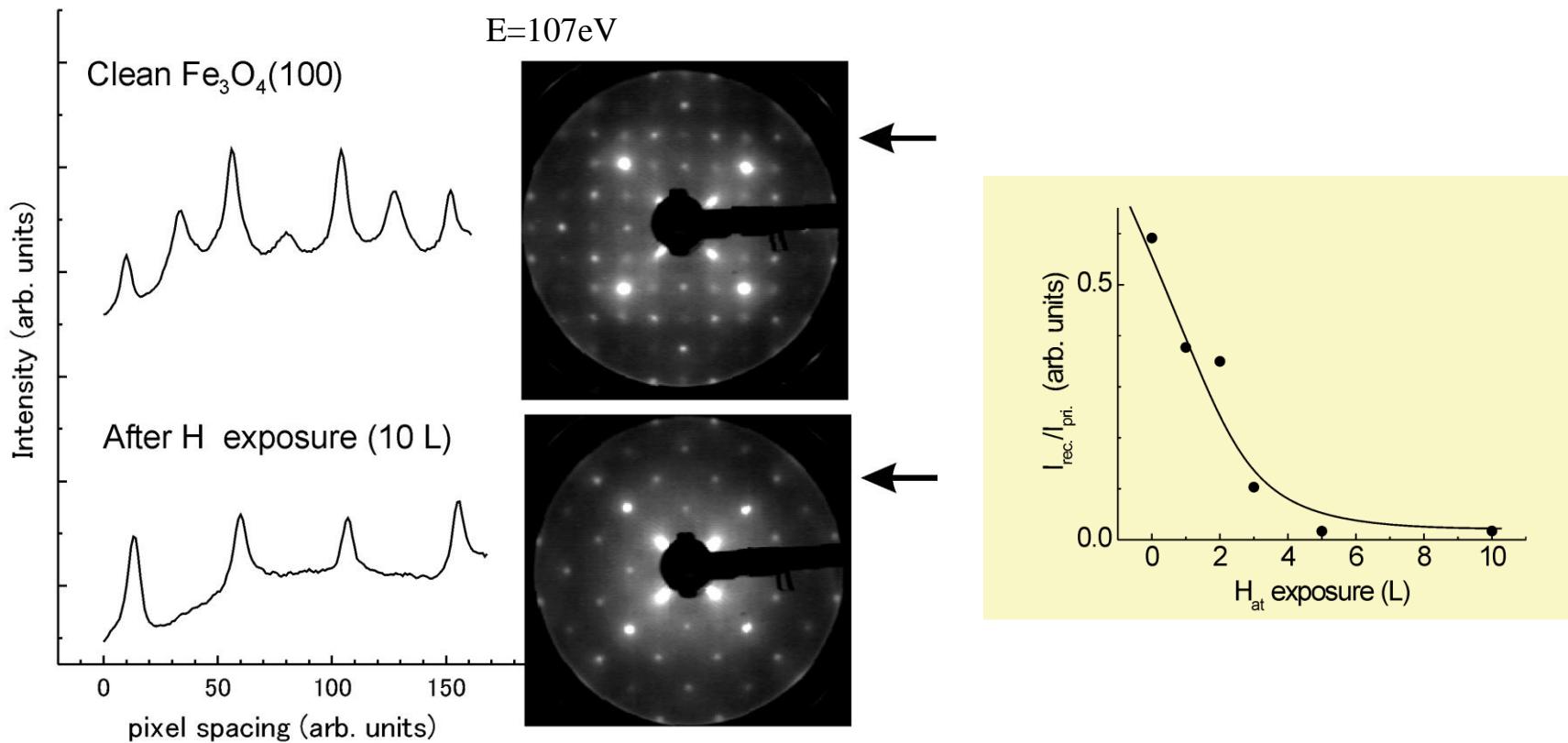


* $\text{Fe}_3\text{O}_4(100)$ clean surface
--low $P(E_F)$

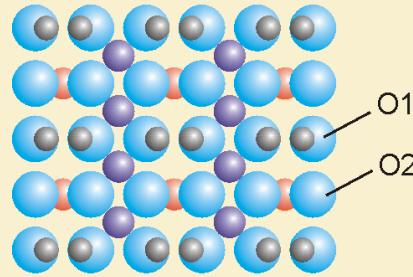
- H termination
→ strong increase in $P(E_F)$

M. Kurahashi et al., Phys. Rev. B, **81**, 193402 (2010).

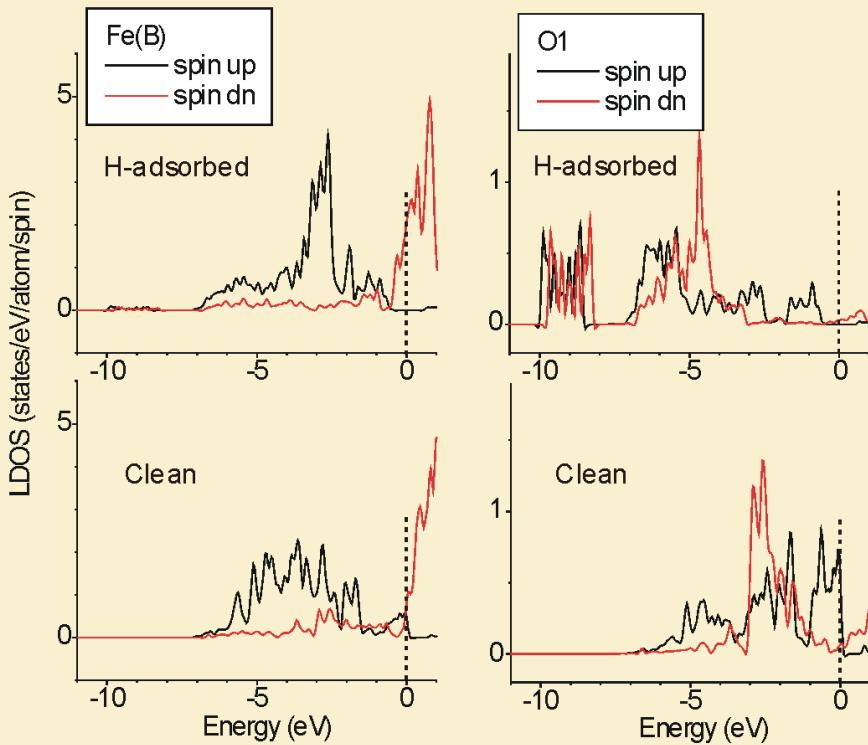
$\text{Fe}_3\text{O}_4(100) / \text{MgO}(100)$: LEED



$\text{Fe}_3\text{O}_4(100) / \text{H}$: DFT calculation



● Fe(B)
● Fe(A)
● O
● H



- ideal B-terminated $\text{Fe}_3\text{O}_4(100)$ surface + H (O1 site)
(*only H position was optimized.)
- O2 site—unfavorable ($\Delta E_{\text{ad}} \sim 0.6$ eV)

- H termination
→ half-metallic at surface Fe(B)
- OH bonding
electron donation to Fe_{\downarrow} band

まとめ、今後の課題

Fe₃O₄(100)最表面フェルミ面スピン偏極

- ・清浄面----低。非対称率は5%以下。
- ・表面の水素終端→ 最表面P(E_F)が著しく増大
(298Kで-50%以上、 計算ではhalf-metallic。)
- ・表面酸素結合状態の変化、水素からの電子供与
→ P(E_F)増大の要因

今後の課題

- ・分子への高スピン偏極誘起
- ・温度依存性、面方位依存性